

AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions and listings of claims in the application:

LISTING OF CLAIMS:

1. (Currently Amended) A plasma etching reactor comprising a reaction chamber (1) surrounded by a leakproof wall (2), said reaction chamber containing a substrate support means (3), and communicating with a plasma source (4), is characterized in that it further comprises said reactor further comprising; a heater liner (14) of an appropriate metal or alloy lining all or at least part of the leakproof wall (2) of the reaction chamber (1) in non-leakproof manner, and an intermediate thermal insulation space (15) provided between the heater liner (14) and the leakproof wall (2) of the reaction chamber (1).

2. (Currently Amended) A reactor according to claim 1, characterized in that the appropriate metal or alloy is selected from metals and alloys that firstly do not react with the fluorine-containing etching gas or the passivation gas to form volatile compounds, and secondly do not emit contaminating atoms under the effect of plasma bombardment.

3. (Currently Amended) A reactor according to claim 2, characterized in that the appropriatesaid metal is aluminum or titanium.

4. (Currently Amended) A reactor according to claim 1, characterized in that it further comprises:

bias means (10, 11) for biasing the substrate support means (3) in order to control bombardment by particles coming from the plasma;

an etching gas source (9a), and means (9b) for controlling the etching flow rate to govern the introduction of etching gas into the plasma source (4);

a passivation gas source (9e), and means for controlling the passivation flow rate (9d) for governing the introduction of passivation gas into the plasma source (4); and

a control device (9e) adapted to cause the etching gas flow rate control means (9b) and the passivation gas flow rate control means (9d) to operate in alternation.

5. (Currently Amended) A reactor according to claim 1, characterized in that the heater liner (14) is fastened to the leakproof wall (2) of the reaction chamber (1) by a small number of ~~fastening points~~fasteners (16a, 16b).

6. (Currently Amended) A reactor according to claim 5, characterized in that the intermediate space between the heater liner (14) and the leakproof wall (2) of the reaction chamber (1) communicate with the central space of the reaction chamber (1) via an annular space (14e) of small thickness.

7. (Currently Amended) A reactor according to claim 5, characterized in that the ~~fastening points~~fasteners (16a, 16b) are of a material which opposes thermally insulating

~~structure opposing the transfer of heat energy by conduction from the heater liner-(14) to the leakproof wall-(2) of the reaction chamber-(1).~~

8. (Currently Amended) A reactor according to claim 5, characterized in that the heater liner-(14) is suspended from the leakproof wall-(2) of the reaction chamber-(1) by three projections having heads, projecting beneath the face of the leakproof wall-(2) and engaged in keyhole-shaped slots each having a wide portion and for passing a head and a narrow portion for retaining the head.

9. (Currently Amended) A reactor according to claim 1, characterized in that the heater liner-(14) is thermally coupled to ~~a heater means such as electrical resistances (17)~~ suitable for connection to an external source of electrical energy.

10. (Currently Amended) A reactor according to claim 9, characterized in that the ~~heater comprises~~ electrical resistances-(17) comprise thin-film electrical resistances and/or electrical resistances of the thermocoaxial type.

11. (Currently Amended) A reactor according to claim 1, characterized in that the heater liner-(14) is heated by radiant heater means such as infrared elements.

12. (Currently Amended) A reactor according to claim 1, characterized in that the heater liner (14) is associated with temperature-regulator means (18-21) for regulating its temperature in a suitabledesired range of temperature values.

13. (Currently Amended) A reactor according to claim 1, characterized in that the heater liner (14) includes a heater means (17) suitable for heating it to a temperature higher than 150°C.

14. (Canceled)

15. (Currently Amended) A reactor according to claim 1, characterized in that downstream from the substrate support means (3) the reaction chamber (1) is limited by a conductive grid (5) in thermal contact with the heater liner (14).

16. (Currently Amended) A reactor according to claim 1, characterized in that the substrate support means (3) comprisecomprises electrostatic electrodes (3a) for attracting the substrate.

17. (Canceled)

18. (Canceled)

Please add the following new claim:

19. (New) A reactor according to claim 2, characterized in that the metal or alloy is selected from metals and alloys that do not emit contaminating atoms under the effect of plasma bombardment.